

BEST SOLUTIONS FOR GaAs APPLICATIONS

ABI Series Effusion Cell with Heating Insert Technology for Ga & In

- Smart heated insert technology
- High loading capacity: from 85cc to 4000cc
- Higher stability than any other effusion cell
- High wafer growth uniformity improved by a factor of 3
- Low defect density compared to any other effusion cell
- Low cost of ownership



VAC Series Valved Arsenic Cracker Source

- Easy to refill, larger capacity, longer growth campaign
- High quality and reliable field-proven design
- Very easy refilling and maintenance operations
- Optimized As consumption leading to longer growth campaigns
- Excellent flux uniformity leading to superior epiwafer quality
- Highly reproducible and precise control of Arsenic flux
- Very large range of loading capacity



VCOR Series Valved Cracker Source for Corrosive Materials (Sb, Mg, Te, Se, etc.)

- Performance, flexibility and reliability
- Highly reproducible flux control
- Full reservoir loading capacity from 110cc to 300cc
- Very simple charge refilling
- No delicate valve parts to dismantle
- Only 2 heating zones sources



Aluminum CL&DZ Series Effusion Cell with Cold Lip Effect for Al

- Extreme stability, no Al creeping
- Group III and particularly Al material evaporation
- Operate in cold lip mode, optimal for Al
- Large choice of Cold Lip and Double zone cells
- Eliminates damages from Al creep with Cold Neck crucible
- Uniformities better than $\pm 1\%$



Carbon Doping Cell Solid Filament Technology



- Control the flux of carbon thanks to the heated pyrolytic graphite filament
- Obtain holes concentration from 10^{18} to 10^{20} cm³ in GaAs
- U.H.V. compliant construction method
- Excellent Uniformity
- Rapid flux variation
- 2000-2300°C Operating temperature range
- Longest life time of the PG filament compared to carbon cells available on the market

DCC Series Double Cluster Cell (Si, Mg, Be, etc.)

- Boost your system capability
- Compact thermal evaporation cell
- Two cells on one port – cluster cell design
- 80 - 1600°C operating temperature range
- Cluster cell operation at different evaporation temperature without any risk of cross contamination
- Integrated water panel and shutter
- Perfect for spintronics applications



For more information, please contact:

RIBER - 31, rue Casimir Périer, B.P 70083, 95873 Bezons, France
Tel: +33 (0)1 39 96 65 00 - Fax: +33 (0)1 39 47 45 62 - email: info@riber.com - Internet: www.riber.com

RIBER